U.S. PTO	
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	Subclass	ISSUE CLASSIFICATION
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U.S. **UTILITY** Patent Application

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	PATENT DATE
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APPLICATION NO. 09/887165	CONT/PRIOR	216 216 2138	SUBCLASS	1746	EXAMINER
Calvin Ga Lynne Oka Ramkumar	ada	ian	:		

N-containing plasma etch process with reduced resist poisoning

		ISSUING C	CLASSIFICATION		
ORIGIN	AL		CROSS REFERENCE(S)		
CLASS	SUBCLASS	CLASS			
INTERNATIONAL	L CLASSIFICATION				
			Continued on Issue Slip Inside File Jacket		

TERMINAL	DRAWINGS			01.415		
DISCLAIMER		DILAWINGS		CLAIMS ALLOWED		
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.	
The Assertation		<u> </u>			J	
The term of this patent subsequent to (date)	ļ			NOTICE OF ALLOWANCE MAILED		
has been disclaimed.	(Assistant Examiner) (Date)					
The term of this patent shall not extend beyond the expiration date						
of U.S Patent. No.				ISSI	JE FEE	
				Amount Due	Date Paid	
	(Primary E	xaminer)	(Date)			
The terminalmonths of this patent have been disclaimed.				ISSUE BAT	CH NUMBER	
	(Legal Instrumer	nts Examiner)	(Date)		Ĭ	
WARNING:						
he information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368.						

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